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Application Number	10/645,306
Filing Date	August 21, 2003
First Named Inventor	Choi, Byung-Jin
Art Unit	1763
Examiner Name	Unassigned
Attorney Docket Number	P86/MII-46-28-03

Total Number of Pages in This Submission

**ENCLOSURES (Check all that apply)**

- |  |   |   |
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| <input type="checkbox"/> Fee Transmittal Form                                | <input type="checkbox"/> Drawing(s)   | <input type="checkbox"/> After Allowance communication to Technology Center (TC)        |
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| <input type="checkbox"/> Certified Copy of Priority Document(s)              | <b>Remarks</b>  | Return Receipt Postcard to Kenneth Brooks   |
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**SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT**

Firm or Individual name	Law Office of Kenneth C. Brooks
Signature	
Date	February 23, 2004

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Choi et al.

Serial No.: 10/645,306

Filing Date: 08/21/2003

For: CAPILLARY IMPRINTING TECHNIQUE

PATENT APPLICATION

Group Art Unit: 1763

Examiner: Unassigned

INFORMATION DISCLOSURE STATEMENT

Commissioner

for Patents

Alexandria, VA 22313-1450

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and a copy of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

<u>Patent Number</u>	<u>Inventor</u>	<u>Grant Date</u>
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09/908,455	Choi et al.	07/17/2001
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<u>Document No.</u>	<u>Inventor</u>	<u>Pub. Date</u>
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- Krug, Herbert et al. "Fine Patterning of Thin Sol-Gel Films," *Journal of Non-Crystalline Solids*, pp. 447-450, 1992.
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Bender, M. et al. "Fabrication of Nanostructures Using a UV-based Imprint Technique," *Microelectronic Engineering*, pp. 223-236, 2000.

Choi, B.J. et al. "Design of Orientation Stages for Step and Flash Imprint Lithography," *Precision Engineering*, vol. 25, pp. 192-199, 2001.

Nguyen, A. Q. "Asymmetric Fluid-Structure Dynamics in Nanoscale Imprint Lithography," University of Texas at Austin, August 2001.

CERTIFICATE OF MAILING

Respectfully Submitted,

I hereby certify that this paper (along with any paper referred to as being attached or enclosed) is being deposited with the United States Postal Service on the date shown below with sufficient postage as first class mail in a package addressed to: MAIL STOP PATENT APPLICATION, Commissioner for Patents, Alexandria, VA 22313-1450

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Date: Feb. 23, 2004

Respectfully,

Kenneth C. Brooks  
Reg. No. 38,393

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Facsimile: 512-527-0107  
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P86/MII-46-28-03

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<sup>1</sup>Unique citation designation number. <sup>2</sup>See attached Kinds of U.S. Patent Documents. <sup>3</sup>Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup>For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the patent document. <sup>5</sup>Kind of document by the appropriate symbols as indicated on the document under WIPO Standard ST. 16 if possible. <sup>6</sup>Applicant is to place a check mark here if English language Translation is attached.

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				Application Number	10/645,306
				Filing Date	08/21/2003
				First Named Inventor	Choi et al.
				Group Art Unit	1763
				Examiner Name	Unassigned
Sheet	3	of	5	Attorney Docket Number	P86/MII-46-28-03

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	A32	COWIE, "Polymers: Chemistry and Physics of Modern Materials," 1991, pp. 408-409, 2 <sup>nd</sup> Ed, Chapman and Hall, a division of Routledge, Chapman and Hall, Inc., 29 West 35 <sup>th</sup> Street, NY, NY 10001-2291.	
	A33	KRUG et al., "Fine Patterning of Thin Sol-Gel Films," Journal of Non-Crystalline Solids, 1992, pp. 447-450, vol. 147 & 148.	
	A34	Kotachi et al., "Si-Containing Positive Resist for ArF Laser Lithography," J. PhotopolymerSci. Tevhnol. 8(4) 615-622, 1995.	
	A35	Krauss et al., "Fabrication of Nanodevices Using Sub-25nm Imprint Lithography," Appl. Phys. Lett 67(21), 3114-3116, 1995	
	A36	CHOU et al., "Imprint of Sub-25 nm Vias and Trenches in Polymers," Applied Physics Letters, November 20, 1995, pp. 3114-3116, vol. 67(21).	
	A37	CHOU et al., "Imprint Lithography with 25-Nanometer Resolution," Science, Apr. 5, 1996, pp. 85-87, vol. 272.	
	A38	HAISMA et al., "Mold-Assisted Nanolithography: A Process for Reliable Pattern Replication," Journal of Vacuum Science and Technology, Nov/Dec 1996, pp. 4124-4128, vol. B 14(6).	
	A39	CHOU et al., "Imprint Lithography with Sub-10nm Feature Size and High Throughput," Microelectronic Engineering, 1997, pp. 237-240, vol. 35.	
	A40	SCHEER et al., "Problems of the Nanoimprinting Technique for Nanometer Scale Pattern Definition," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3917-3921, vol. B 16(6).	
	A41	XIA et al., "Soft Lithography," Annu. Rev. Mater. Sci., 1998, pp. 153-184, vol. 28.	
	A42	XIA et al., "Soft Lithography," Agnew. Chem. Int. Ed., 1998, pp. 550-575, vol. 37.	

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Sheet	4	of	5	Attorney Docket Number	P86/MII-46-28-03

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	A43	WU et al., "Large Area High Density Quantized Magnetic Disks Fabricated Using Nanoimprint Lithography," Journal of Vacuum Science and Technology, Nov/Dec 1998, pp. 3825-3829, vol. B 16(6).	
	A44	COLBURN. et al., "Step and Flash Imprint Lithography: A New Approach to High-Resolution Patterning", Proc. of SPIE, 1999, pp. 379-389, vol. 3676.	
	A45	CHOU et al., "Lithographically-Induced Self Assembly of Periodic Polymer Micropillar Arrays," Journal of Vacuum Science and Technology, Nov/Dec 1999, pp. 3197-3202, vol. B 17(6).	
	A46	RUCHHOEFT et al., "Patterning Curved Surfaces: Template Generation by Ion Beam Proximity Lithography and Relief Transfer by Step and Flash Imprint Lithography," Journal of Vacuum Science and Technology, 1999, pp. 2965-2982, vol. 17.	
	A47	CHOI et al., "Design of Orientation Stages for Step and Flash Imprint Lithography," Precision Engineering, Journal of the International Societies for Precision Engineering and Nanotechnology, 2001, pp. 192-199, vol. 25.	
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	A51	BENDER M. et al., "Fabrication of Nanostructures using a UV-based Imprint Technique," Microelectronic Engineering, pp 223-236, 2000.	
	A52	SREENIVASAN et al., "High-Resolution Overlay Alignment Methods and Systems for Imprint Lithography," U.S. Patent Application 09/907,512, Filed with USPTO on July 16, 2001.	
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Sheet	5	of	5	Attorney Docket Number	P86/MII-46-28-03

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Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	A54	CHOI et al., "Methods for High-Precision Gap and Orientation Sensing Between a Transparent Template and Substrate for Imprint Lithography," U.S. Patent Application 09/920,341, Filed with USPTO on August 1, 2001.	
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